

Limited Tender for a Metal Sputtering Deposition Unit.

Only Indian manufacturers of the system are allowed to participate.

CeNSE is a multidisciplinary research department at IISc that houses a 14,000 sq. ft. cleanroom and characterization facility used by 50 faculty members from various disciplines at IISc. Consequently, any tool in CeNSE receives significant exposure to scientific community at IISc and beyond. The vendors are requested to factor in the value of this exposure in to their quotes.

http://nnfc.cense.iisc.ac.in/

http://www.mncf.cense.iisc.ac.in/

https://www.inup.cense.iisc.ac.in/

Procedure

- 1. Vendors will be required to submit a technical proposal and a commercial proposal in **two separate sealed envelopes**. Only vendors who meet the technical requirement will be considered for the commercial negotiation.
- 2. **The deadline for submission of proposals is 16th April 2021 5 PM.** Proposals should arrive at the National Nanofabrication Centre (NNFC), Indian Institute of Science, Bangalore 560012, India, by the above deadline.
- 3. The decision of purchase committee will be final.
- 4. The technical proposal should contain a compliance table with 5 columns. The first column must list the technical requirements, in the order that they are given in the technical configuration below. The second column should describe your compliance in a "Yes" or "No" response. If "No" the third column should provide the extent of the deviation (please provide quantitative responses). The fourth column should state the reasons for the deviation, if any. The fourth column can be used to compare your tool with that of your competitors or provide details as requested in the technical requirements table below.
- 5. Any additional capabilities or technical details, that you would like to bring to the attention of the purchase committee, can be listed at the end of the technical table.

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- 6. Vendors are encouraged to highlight the advantages of their tools over comparable tools from the competitors.
- 7. If multiple systems can fulfil the requirements, vendors can submit multiple bids.
- 8. In the commercial bid, please provide itemized cost of the system and required accessories, such as software, power supply, etc.
- 9. As an option, please provide itemized cost for any suggested accessories/add-ons that may enhance the usability, capability, accuracy or reliability of the tool. Vendors are encouraged to quote for as many add-ons as their tool portfolio permits.
- 10. The quotes should be FOR Indian Institute of Science, Bangalore in Indian Rupee only.
- 11. Please indicate the warranty provided with the tool. **Warrant of 1 year** is preferred.
- 12. Provide itemized cost for required spares for 2 years of operation. For sake of this calculation, the vendor may assume active tool usage of 20 hours/week. This number will be used to estimate the life cycle cost of the tool.
- 13. If maintenance requires, as an additional option, provide cost of an annual maintenance contract (AMC) for 3 years, post warranty. The **AMC must cover 2 scheduled and 2 emergency visits per year**. The AMC cost must also include an itemized list of spares that are essential for the scheduled visits.
- 14. The **RFQ** must include references of minimum 5 previous installations, preferable in India. Please provide the names and contact addresses of the referees, so that the committee can contact them independently.
- 15. Any technical questions can be directed to S. Varadharajaperumal (varadhu@iisc.ac.in), Technology Manager, NNFC, IISc., Bengaluru and Dr. Savitha (savithap@iisc.ac.in), COO, NNFC, IISc., Bengaluru.



Technical Requirements

	l echnical Requirements			
1.	Primary application	• DC magnetron sputtering system for thin film deposition (metals such as Al, Au, Ni and Ti).		
2.	Magnetron	a). <u>Vacuum Chamber:</u>		
	Sputtering System	Material of Construction (MOC): SS 304 grade or better.		
		Chamber size: Approximately 500 mm (W) X 500 mm (D) X 500 (H)		
		[minimum requirement].		
		A front opening quick access door for loading & unloading of the		
		substrates and materials. Removable chamber top plate with vacuum		
		penetrations.		
		Necessary ports required for pumping, magnetrons, Gas Inlet, vent,		
		gauge, feedthrough, and rotation mechanism etc.		
		One high vacuum compatible, toughened glass view port with a manual		
		shutter to avoid material deposition on the view port on the door.		
		One set of removable stainless steel liners for easy cleaning.		
		b). Magnetron Sources:		
		• Four numbers of 3" Dia. indirectly water cooled circular magnetron		
		cathode with bellows for flexibility.		
		Confocal type with sputter up arrangement.		
		 Provision for substrate to target distance is required. 		
		Electro pneumatically operated shutter for each magnetron source.		
	c).	c). Substrate Holder & Rotation:		
		A substrate holder should handle up to a 6-inch dia. substrate. Also		
		permit to place small irregular pieces of wafers (suitable clips should		
		be provided to hold samples onto the holder).		
		• The thickness uniformity should be ±5% over 100mm (6 inch)		
		diameter substrate. A measurement certificate of thickness uniformity		



	of any metal (for example Al/Au/Ag) on Si substrate of appropriate			
	size should be provided. The thickness should be measured using			
	standard characterization techniques showing variation of thickness			
	along the radius of the Si substrate. The committee reserves the right			
	to verify the certificate and thickness uniformity at the customer			
	site/manufacturer site. Manufacturer has to arrange the necessary			
	facilities for assessing uniformity.			
•	Motorized linear Z movement.			
•	Substrate rotational capability with adjustable speed up to 20rpm.			
d). <u>D(</u>	C Power Supply:			
•	One number of DC 1.5kW power supply of good quality (imported)			
	with necessary cables and connectors for magnetron sputtering.			
•	1 IN 4 OUT DC Switch box.			
a). <u>Hi</u>	 Substrate rotational capability with adjustable speed up to 20rpm. DC Power Supply: One number of DC 1.5kW power supply of good quality (imported) with necessary cables and connectors for magnetron sputtering. 1 IN 4 OUT DC Switch box. High vacuum pump: 			
•	A Turbo molecular pump (LEYBOLD/ALCATEL/VARIAN/			
	EDWARDs or equivalent) having suitable pumping speed (minimum			
	500 lit/sec) to achieve chamber vacuum level at least 5x10-7 mbar.			
•	Ultimate Pressure: < 5x10-7 mbar to be achieved			

Vacuum Pumping System

a). H

- Ultimate Pressure: $\leq 5x10-7$ mbar to be achieved.

b). Dry Scroll pump:

• Dry scroll pump (10 m³/hr or higher) (Make ANESTA IWATA/ LEYBOLD / EDWARD / VARIAN or equivalent) for roughing and backing operations.

c). Vacuum and High Vacuum Valves:

- Electro pneumatically operated right angle for roughing, backing and high vacuum applications.
- Vent valve, fine control needle valves to be provided.
- Three positions, electro pneumatically operated gate valve.



		c). <u>Vacuum Gauges:</u>
		Imported Pirani & Penning Gauges for vacuum measurement.
4.	Safety and	Electrical overload protection.
	Interlocks	Mains Indication lamp.
		Emergency ON/OFF Switch.
		Vacuum switch interlocked with cathode power supply for avoiding
		switching-ON of power sources without vacuum. Safety panel
		switches to cut off source power supply, if doors open.
		A water flow switch in the water circulation line of the unit protects the
		turbo molecular pump incase of water supply failure/low pressure by
		switching off the turbo molecular pump.
		All major electrical circuit is provided with fuse.
		All major components will be connected through circuit breaker and
		contactor.
5.	Process gas	Mass flow controlled gas line for Argon to control flow upto 200 sccm
	manifold	with isolation valves and filter.
		Ar gas line should be plumbed to all the 3" sources, with control valves
		to directs the flow to one or all sources.
		Pressure control during deposition - Multi-position/Butterfly valve
		based automatic controller.
6.	Control panel	System should have a high stability, industrial grade PLC.
		User Operation should be using touch screen HMI.
		The system should have easy-to-use & intuitive software.
		System Operation via a menu-driven interface.
		Users are able to edit, save and load multiple recipes.
7.	Utilities	Details to be provided in the offer for space, power supply, gas, etc for
		system operation.



8.	Inspection and	The vendor or the OEM has to demonstrate the following during the pre-
	Acceptance Test	dispatch inspection,
		• Ultimate vacuum of 5 x 10 ⁻⁷ mbar in clean empty chamber.
		• The vacuum leak rate of 3 x10 ⁻⁹ std. cc/sec. using MSLD.
		• The thickness uniformity ±5% or better over a 6 inch substrate.
9.	Warranty	12 months from the date of commissioning and acceptance of equipment.
10.	Eligibility Criteria	The bidder must have supplied similar systems to at least 10
		educational institutes/universities and/or research organizations and at
		least five to the CFTI's in India along with contact details.
		Original Invoice, Original Warranty Certificate, Original Test Reports
		should be produced for all imported items from OEM (Original
		Equipment Manufacturer) at the time of supply of the equipment.
		System Catalogue should be produced with the Technical Bid.
		CE Certification must be provided for the proposed system. The CE
		certificate should be provided with the Unit.
		Manufacturer should have ISO or equivalent international standard
		certificate.
		Supplier will support the user with all the spares for a minimum period
		of 10 years.
		Details of experienced service engineer including contact detail should
		be provided in tender document.
		Bidder shall have to submit audited accounts (Balance sheet profit and)
		loss account) of financial year 2017-18, 2018-19 and 2019-20. Audited
		statement must be signed and stamped by qualified chartered
		accounted. Income Tax return for assessment year – 2017-18, 2018-19
		and 2019-20.
		Up to date sales tax or GST clearance certificate.
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informity $\pm 5\%$ or better over a 6-inch substrate.
with uniformity and thickness measurement report
ed along with the bid.
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Thanking you,

Faculty